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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/590,046	06/15/2007	Taku Hirayama	SHIGA7.055APC	5635
20995 7590 09/26/2008 KNOBBE MARTENS OLSON & BEAR LLP			EXAMINER	
2040 MAIN ST		JOHNSON, CONNIE P		
FOURTEENTH IRVINE, CA 92			ART UNIT	PAPER NUMBER
			1795	
			NOTIFICATION DATE	DELIVERY MODE
			09/26/2008	ELECTRONIC

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

jcartee@kmob.com eOAPilot@kmob.com

	Application No.	Applicant(s)
	10/590,046	HIRAYAMA
Office Action Summary	Examiner	Art Unit
	CONNIE P. JOHNSON	1795
The MAILING DATE of this communication ap Period for Reply	ppears on the cover sheet with the c	correspondence address
A SHORTENED STATUTORY PERIOD FOR REPLEWHICHEVER IS LONGER, FROM THE MAILING ID. - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period. - Failure to reply within the set or extended period for reply will, by statuly Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATION .136(a). In no event, however, may a reply be tird d will apply and will expire SIX (6) MONTHS from te, cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).
Status		
Responsive to communication(s) filed on 15 c This action is FINAL . 2b) ☐ This action is FINAL . Since this application is in condition for allowatelessed in accordance with the practice under	is action is non-final. ance except for formal matters, pro	
Disposition of Claims		
4) Claim(s) 1-15 is/are pending in the application 4a) Of the above claim(s) is/are withdra 5) Claim(s) is/are allowed. 6) Claim(s) 1-15 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/ Application Papers 9) The specification is objected to by the Examin 10) The drawing(s) filed on is/are: a) ac Applicant may not request that any objection to the	awn from consideration. For election requirement. Here. Here is a consideration in the second consideration.	
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E	· · · · · · · · · · · · · · · · · · ·	, ,
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreig a) All b) Some * c) None of: 1. Certified copies of the priority documer 2. Certified copies of the priority documer 3. Copies of the certified copies of the priority documer application from the International Burea * See the attached detailed Office action for a list	nts have been received. nts have been received in Applicationity documents have been received au (PCT Rule 17.2(a)).	on No ed in this National Stage
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date 8/12/08,6/24/08,4/8/08 and 8/17/06.	4) Interview Summary Paper No(s)/Mail D: 5) Notice of Informal F 6) Other:	ate



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DETAILED ACTION

Priority

1. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Claim Status

2. Claims 1-15 are presented.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 4. Claims 1-9, 11 and 13-14 are rejected under 35 U.S.C. 102(b) as being anticipated by Watanabe et al., JP 09-160246.

Watanabe teaches a chemically amplified resist composition comprising a compound which has two or more phenolic hydroxyl groups, a photoacid generator and a nitrogen-containing compound (page 10, [0015] and page 25, [0074]). The compound comprising a polyhydric phenol compound with two or more phenolic hydroxyl groups, has a molecular weight of 100 to 1,000 (page 10, [0015]) and has a molecular weight polydispersity of 1.0-1.5 (page 17, [0046]). Compound [DRR10] meets the limitations of a polyhydric phenol compound with two or more phenolic hydroxyl groups as in formula (II) in claim 2 of the present invention (page 39). The polyhydric phenol compounds are protected with acid dissociable groups (page 17, [0046]). The polyhydric phenol

compound also has 60% or less of unprotected phenolic hydroxyl groups (page 3, [claim 2]). The recitation in claim 1, "an ability to form an amorphous film using a spin coating method," is intended use. Since Watanabe teaches the resist composition comprising a compound with two or more phenolic hydroxyl groups, a photoacid generator and a nitrogen-containing compound, then the composition of Watanabe would be capable of forming an amorphous film using a spin coating method (MPEP 2106). Watanabe also teaches a method of patterning the resist comprising forming a resist film, prebaking, exposing, post baking and developing the resist with an alkaline solution (page 27, [0081]).

Claim Rejections - 35 USC § 103

- 5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 6. Claims 8, 10, 12 and 15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Watanabe et al., JP 09-160246 in view of Adegawa et al., JP 2002-312055.

Watanabe teaches a chemically amplified resist composition comprising a compound which has two or more phenolic hydroxyl groups, a photoacid generator and a nitrogen-containing compound (page 10, [0015] and page 25, [0074]). The compound comprising a polyhydric phenol compound with two or more phenolic hydroxyl groups,

has a molecular weight of 100 to 1,000 (page 10, [0015]) and has a molecular weight polydispersity of 1.0-1.5 (page 17, [0046]). Compound [DRR10] meets the limitations of a polyhydric phenol compound with two or more phenolic hydroxyl groups as in formula (II) in claim 2 of the present invention (page 39). The polyhydric phenol compounds are protected with acid dissociable groups (page 17, [0046]). Watanabe does not teach a polyhydric phenol with the structure of formula 4 in claim 10.

Adegawa teaches a positive resist composition comprising a resin with a structure as in formula (4) of claim 10 in the present invention (page 2, formula 1). The resin comprises a compound with two or more phenolic hydroxyl groups and a molecular weight of 1,000 or less (page 49, [0243]). The composition also comprises a nitrogen-containing compound (page 17, [0081]). Adegawa also teaches the composition comprises a photoacid generator (page 11, [0030]). It would have been obvious to use the polyhydric phenol compound in the resist composition of Watanabe because Adegawa teaches resist compositions comprising a low-molecular weight polyhydric phenol with a structure of formula 1 have improved sensitivity and high resolving power (page 6, [0005]).

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to CONNIE P. JOHNSON whose telephone number is (571)272-7758. The examiner can normally be reached on 7:30am-4:00pm Monday thru Friday.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Connie P. Johnson Examiner Art Unit 1795

/Cynthia H Kelly/

Supervisory Patent Examiner, Art Unit 1795